

REMARKS

Claims 1, 2, 5, 6, 20, 21, 27 and 28 are pending in this application. By this Amendment, claim 20 is amended. Reconsideration is respectfully requested.

The Office Action objects to the specification for characterizing P⁺ region 156 as the base of the NPN lateral bipolar transistor. By this Amendment, the specification is amended to clarify that the base region is formed of the B¹¹⁺ doped region 150 and its surroundings in the P-type well. The specification then distinguishes between the base region 150, and the base contact 156. Applicants therefore respectfully request that the objection to the specification be withdrawn.

The Office Action objects to Figs. 1, 23, 24 and 28 for failing to show the first isolation region. By this Amendment, Figs. 1, 23, 24 and 28 are amended to show the first isolation region identified with reference number 300, and the specification is amended to include the reference number in the paragraph beginning on page 22, line 22. Applicants submit that no new matter is added, as the first isolation region is identified in Figs. 4-22 and described throughout the specification as well as in the claims.

The Office Action objects to Figure 22 for not showing the first N-type diffusion region, the second N-type diffusion region and the first isolation region. By this Amendment, reference numeral 114 is added to identify the first N-type diffusion region and reference numeral 154 is added to identify the second N-type diffusion region, and reference numeral 300 corresponds to the first isolation region. Applicants respectfully request that the objection to the drawings be withdrawn.

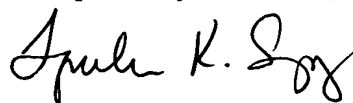
The Office Action rejects claims 20-21 under 35 U.S.C. §112, first and second paragraphs. By this Amendment, claim 20 is amended to recite a second "P-type diffusion region which is isolated by a third isolation region from the second N-type diffusion region," thereby providing antecedent basis for the first to third isolation regions in line 21 of claim

20, and clarifying that the isolation is performed by the isolation region rather than by a third diffusion region. Accordingly, Applicants respectfully request that the rejection of claims 20 and 21 under 35 U.S.C. §112, first and second paragraphs, be withdrawn.

Applicants gratefully acknowledge the Office Action indication that claims 1, 2, 6, 7, 27 and 28 are allowable subject to the removal of the grounds for objection to the specification and drawings, and that claims 20 and 21 are allowable subject to the removal of the rejection under 35 U.S.C. §112, first and second paragraphs. In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 1, 2, 6, 7, 20, 21, 27 and 28 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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JAO:JKS/tea
Attachments:
Replacement Sheets

Date: May 11, 2004

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